

Docket No.: 006217 USA/Consilium/Consilium

PATENT/OFFICIAL

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re Application of :
: Nicholas A. WARD et al. :
: Serial No. 09/927,444 : Group Art Unit: 2125
: Filed: August 13, 2001 : Examiner: Sean P. Shechtman

For: DYNAMIC CONTROL OF WAFER PROCESSING PATHS IN SEMICONDUCTOR
MANUFACTURING PROCESSES

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed after a Request for Continued Examination, before the mailing date of a first Office Action on the merits or Notice of Allowance. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed

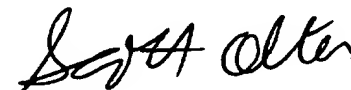
Serial No. 09/927,444

documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right to present to the Office the relevant facts and law regarding the appropriate status of such document.

No fee is believed to be required, however, the Commissioner is hereby authorized to charge any additional fees that may be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,


Wilmer Cutler Pickering Hale and Dorr LLP



Scott M. Alter

Registration No. 32,879

The Willard Office Building
1455 Pennsylvania Avenue, NW
Washington, DC 20004
TEL (202) 942-8428 SMA/lrm
FAX (202) 942-8484
Date: 10/6/04

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| INFORMATION DISCLOSURE CITATION IN AN APPLICATION  (PTO-1449) | | | | ATTY. DOCKET NO. 006217 USA/ Consilium/Consilium | | SERIAL NO. 09/927,444 | |
| | | | | APPLICANT Nicholas A. WARD et al. | | | |
| | | | | FILING DATE August 13, 2001 | | GROUP 2125 | |
| U.S. PATENT DOCUMENTS | | | | | | | |
| EXAMINER'S INITIALS | PATENT NO. | DATE | NAME | CLASS | SUBCLASS | FILING DATE | |
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| EXAMINER | | | | DATE CONSIDERED | | | |

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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| <p align="center">INFORMATION DISCLOSURE CITATION IN AN APPLICATION</p> <p align="center">(PTO-1449)</p> | | ATTY. DOCKET NO. 006217 USA/ Consilium/Consilium | SERIAL NO. 09/927,444 |
| | | | |
| | | APPLICANT Nicholas A. WARD et al. | |
| | | FILING DATE August 13, 2001 | GROUP 2125 |
| OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) | | | |
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